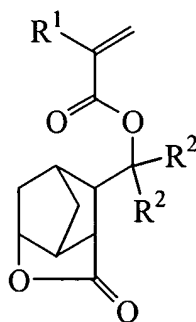


LISTING OF CLAIMS

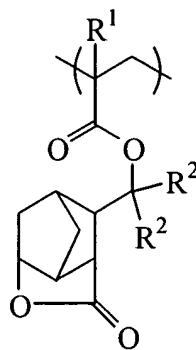
1. (original) A (meth)acrylate compound having the general formula (1):



(1)

wherein R¹ is hydrogen or methyl, and R² is a straight, branched or cyclic monovalent hydrocarbon group having 1 to 10 carbon atoms, or two R² may bond together to form a ring with the carbon atom to which they are bonded.

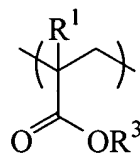
2. (original) A polymer comprising recurring units of the general formula (1a) and having a weight average molecular weight of 2,000 to 100,000,



(1a)

wherein R^1 is hydrogen or methyl, and R^2 is a straight, branched or cyclic monovalent hydrocarbon group having 1 to 10 carbon atoms, or two R^2 may bond together to form a ring with the carbon atom to which they are bonded.

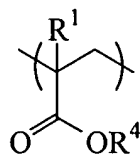
3. (original) The polymer of claim 2, further comprising recurring units of at least one type having the general formula (2a):



(2a)

wherein R^1 is hydrogen or methyl, and R^3 is a tertiary alkyl group of 4 to 20 carbon atoms which may contain a hydroxyl group, carbonyl group, ester bond or ether bond.

4. (original) The polymer of claim 3, further comprising recurring units of at least one type having the general formula (3a):



(3a)

wherein R^1 is hydrogen or methyl, and R^4 is an alkyl group of 2 to 20 carbon atoms which may contain a hydroxyl group, carbonyl group, ester bond, ether bond or cyano group.

5. (original) The polymer of claim 2 wherein the recurring units of formula (1a) are present in a molar fraction of at least 5%.

6. (original) A resist composition comprising the polymer of claim 2.

7. (original) A resist composition comprising

- (A) the polymer of claim 2,
- (B) a photoacid generator, and
- (C) an organic solvent.

8. (original) A resist composition comprising

- (A) the polymer of claim 2,
- (B) a photoacid generator,
- (C) an organic solvent, and
- (D) a basic compound.

9. (original) A process for forming a resist pattern comprising the steps of:

applying the resist composition of claim 6 onto a substrate to form a coating,

heat treating the coating and then exposing it to high-energy radiation having a wavelength of up to 300 nm or electron beams through a photomask, and
heat treating the exposed coating and developing it with a developer.

10. (new) 3-(1-methacryloyloxy-1-methylethyl)-2,6-norbornane carbolactone.